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TECHNICAL DATA SHEET

PRODUCT: BULK EMULSION - UNDERGROUND (E1000UG)

Bulk Underground is Bulk Emulsion with higher content of oxidizer percentage compares with other TKSB's bulk emulsions. The product is sensitised with pre-blend gassing solution to lower its density from 1.36 - 1.44 g/cc to 0.90 - 1.25 g/cc.

After sensitisation, the product is booster sensitive and used as the horizontal or anti gravity charge in various blasting application. It works remarkably well for wet, and wet/dry blast-holes in tunnelling and under ground project with its excellent water resistance.

Product Properties

Description	E1000UG
Bulk Blend Density (g/cc, optimum)	1.05
Minimum diameter (mm)	40
Water Resistance	Excellent
Velocity of Detonation (m/s, approx)	4,500
Sleep Test	7 Days
Energy (MJ/kg) ¹	3.0
Relative volume strength (ANFO = 100) ¹	108

Bulk Underground can be effectively primed with EMULEX® E180 in not smaller than 25 mm diameter chub. The booster diameter and total number of boosters will vary with the rock formation and size of boreholes.

Note: 1. Calculation based on thermodynamic properties.

Sensitising System

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Acid solution	Diluted solution of acetic acid
Gassing emulsion	Diluted solution of sodium nitrite

Note: Gassed density 0.95 – 1.05 g/cc within 5min

Disclaime

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